



US00D868181S

(12) **United States Design Patent** (10) **Patent No.:** **US D868,181 S**
Lee (45) **Date of Patent:** **** Nov. 26, 2019**

(54) **MASK FOR DISGUISE**

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(72) Inventor: **Byung Doo Lee**, Gangneung-si (KR)

(**) Term: **15 Years**

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(80) **Hague Agreement Data**

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(52) **U.S. Cl.**
USPC **D21/660**

(58) **Field of Classification Search**
USPC D24/110.1; D29/108-111; D21/659,
D21/660; 2/173, 206; D2/865, 866, 869,
D2/870

CPC A41G 7/00; A41G 7/02; A41D 13/11
See application file for complete search history.

(56) **References Cited**

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Primary Examiner — Melanie Pellegrini

(57) **CLAIM**

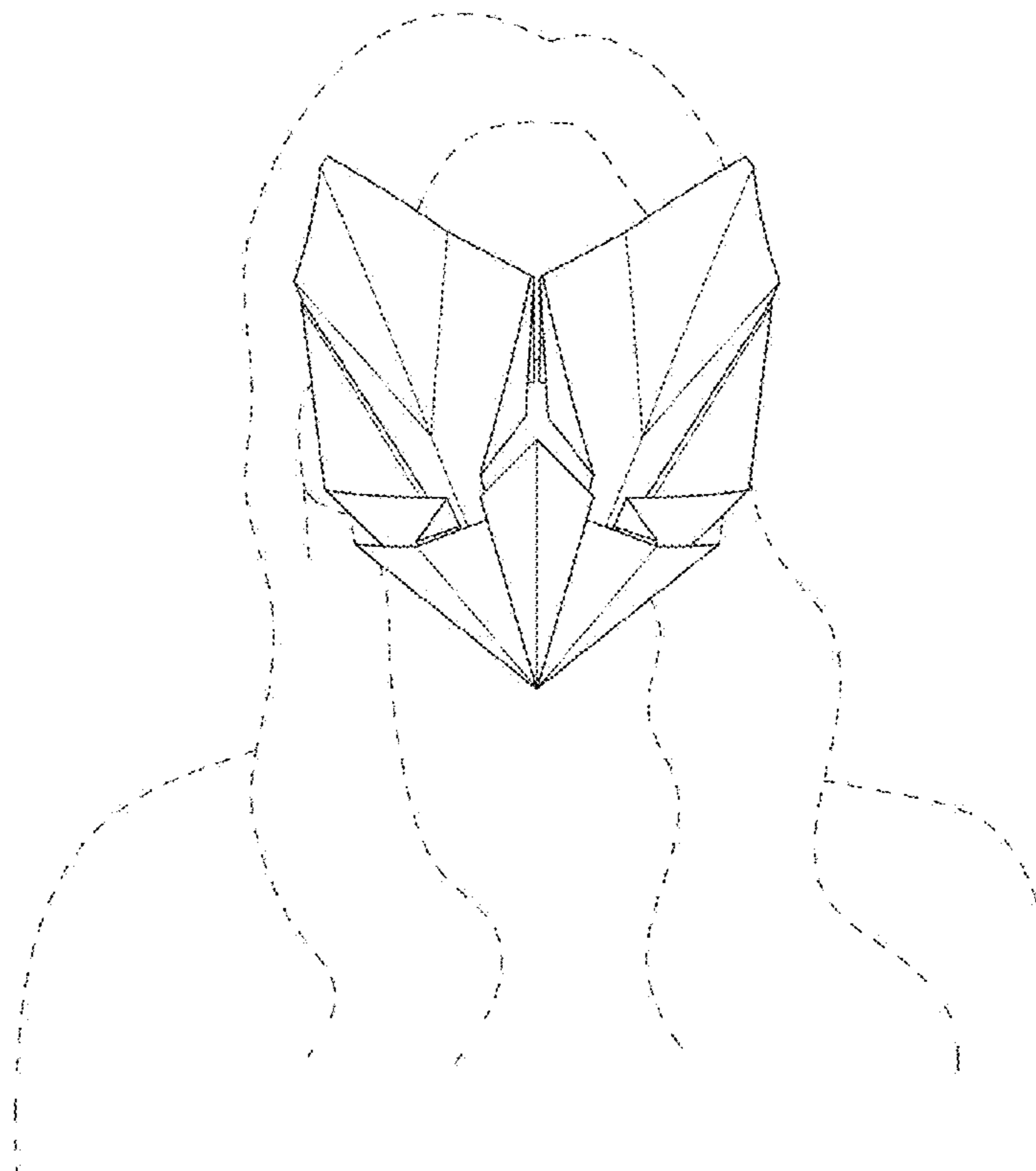
The ornamental design for a mask for disguise, as shown and described.

DESCRIPTION

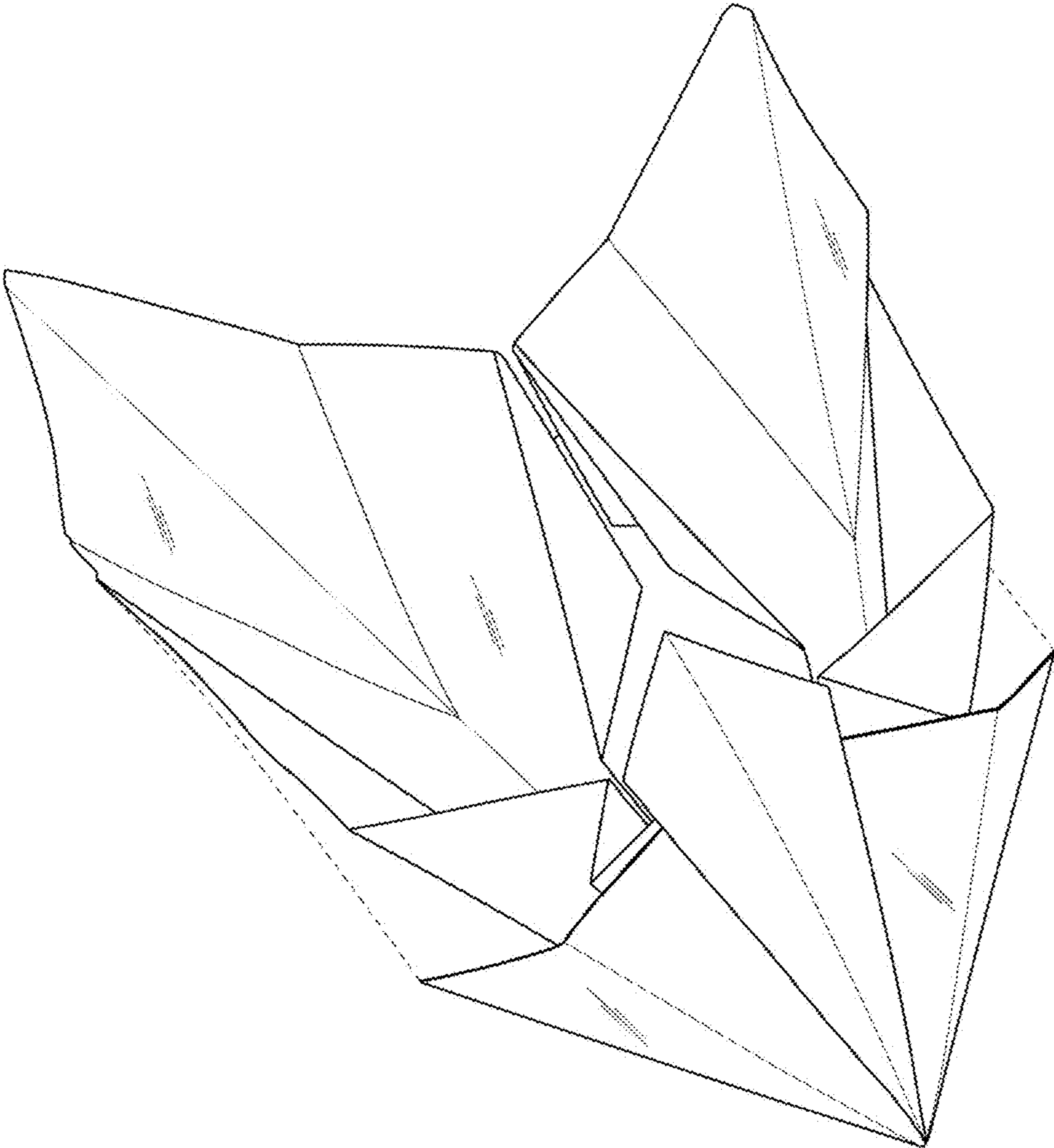
- 1. Mask for disguise
- 1.1 : Perspective
- 1.2 : Front
- 1.3 : Left
- 1.4 : Right
- 1.5 : Top
- 1.6 : Bottom
- 1.7 : Reference

The broken lines shown in the drawings illustrate portions of the mask for disguise and the broken lines showing a human figure in Fig. 1.7 represent environment. The broken lines form no part of the claimed design.

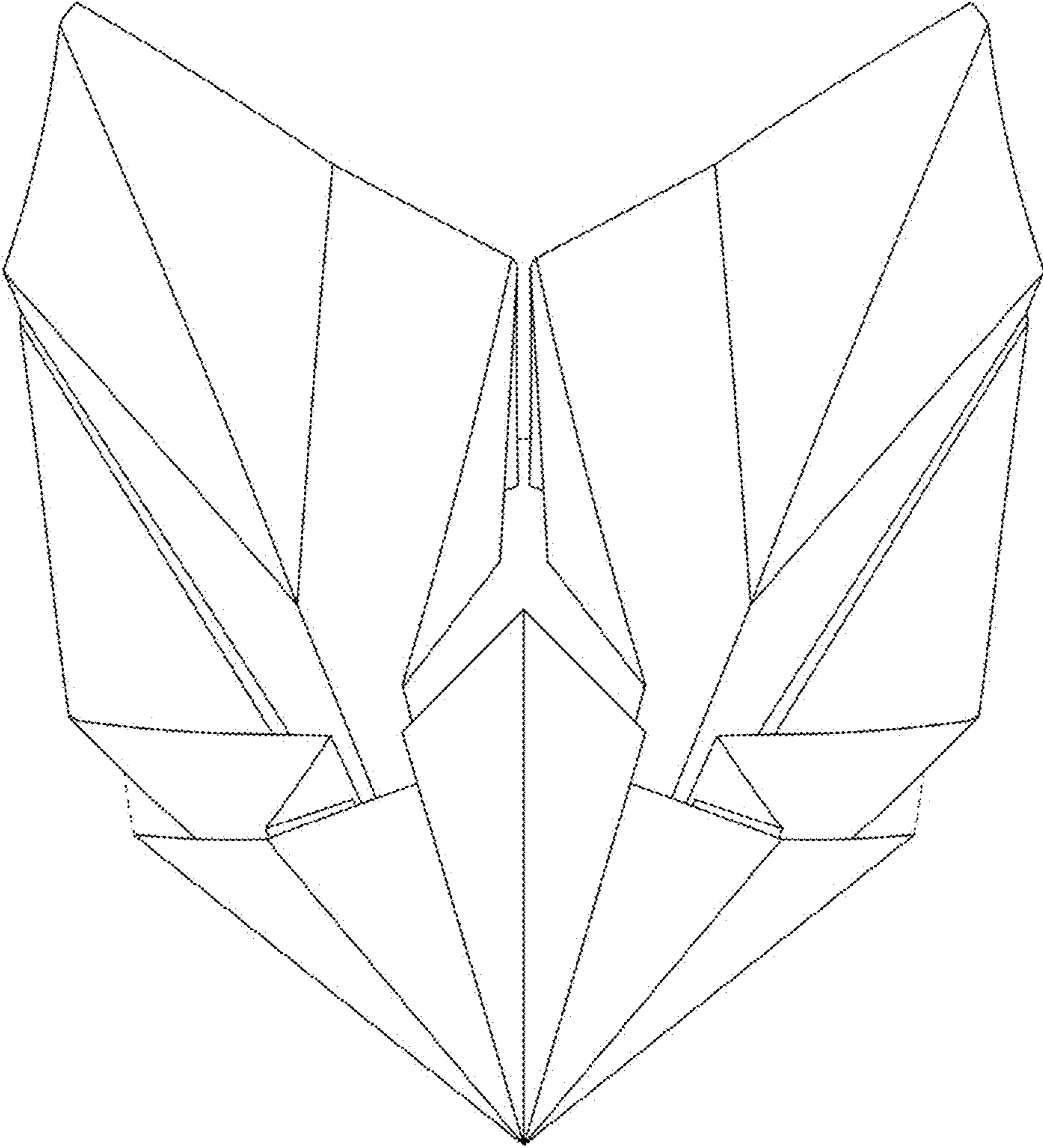
1 Claim, 7 Drawing Sheets



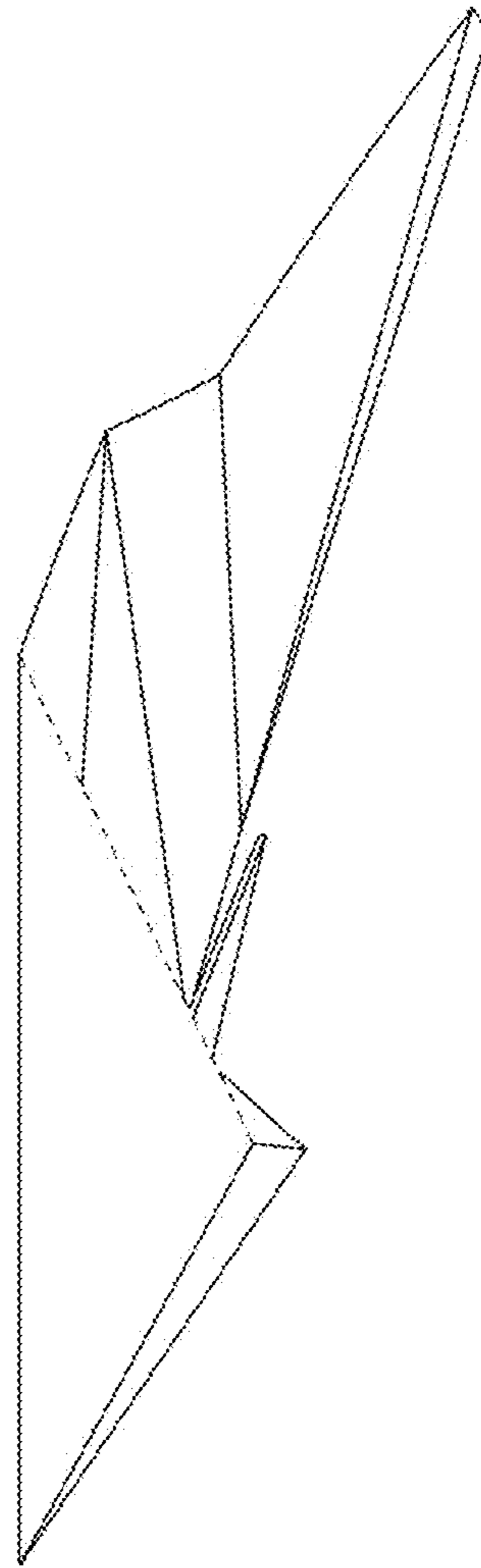
1.1



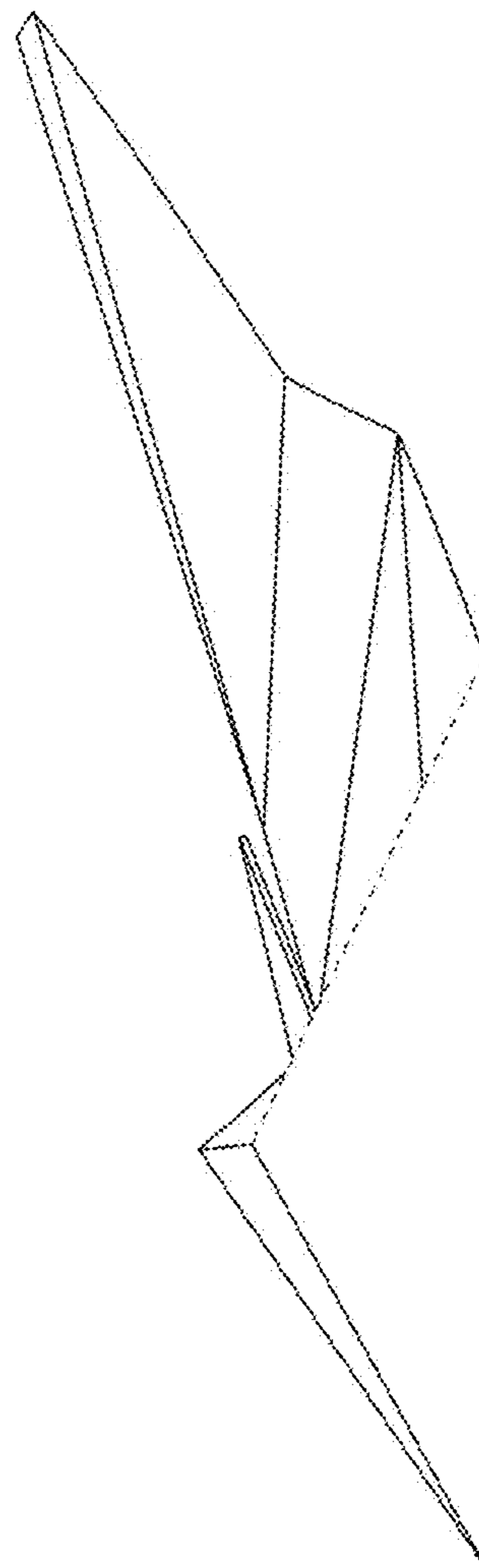
1.2



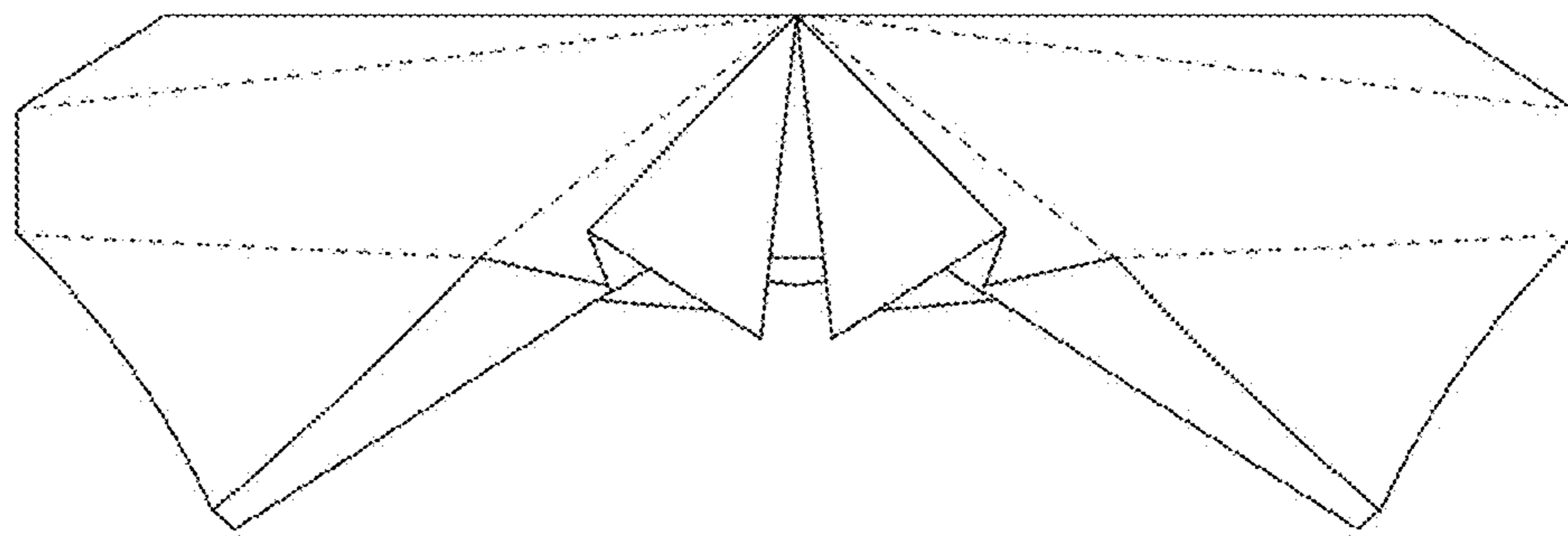
1.3



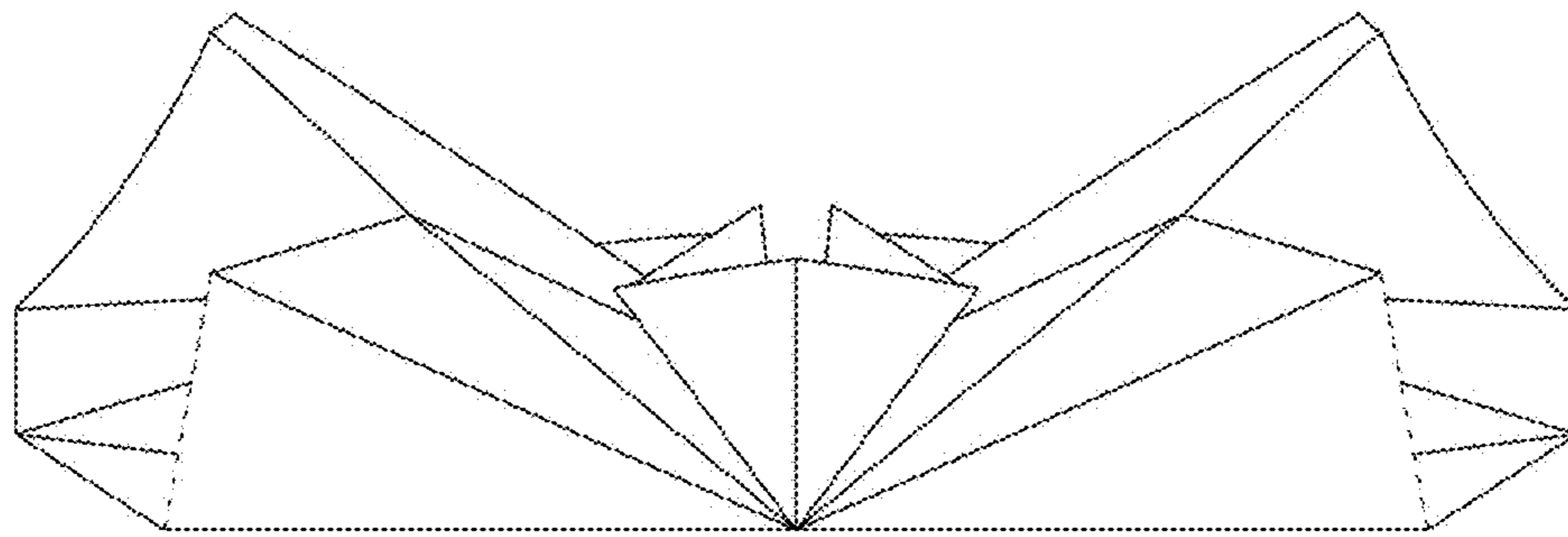
1.4



1.5



1.6



1.7

